

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	1975764	photosensitive resin composition and polyimide and (photosensitizer or initiator)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/02/21 22:46
L2	406373	L1 and o quinone diazide	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/02/21 22:46
L3	2325025	L2 and (?trihydroxybenzophenone o naphthoquinone diazide sulfonic ester) and resin composition	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/21 23:02
L4	406016	L1 and o quinone diazide and 3	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/02/21 22:48
L5	400015	L2 and (?trihydroxybenzophenone o naphthoquinone diazide sulfonic ester)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/02/21 22:49
L6	31944	L5 and cyclohexane and 4	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/02/21 22:49
L7	31948	L5 and cyclohexane	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/02/21 22:50
L8	32	L7 and 522/164.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/02/21 22:50
L9	32	L8 and (polyamic acid or polyimide precursor or polyamide acid) and 6	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/02/21 23:01
L10	32	L8 and (polyamic acid or polyimide precursor or polyamide acid)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/02/21 22:51
L11	28	L10 and (film or layer)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/02/21 22:51

L12	13	L11 and alicyclic	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/02/21 22:51
L13	31	L12 and sulfonic ester and 9	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2005/02/21 22:51
L14	10	L7 and (polyamic acid or polyimide precursor) and photoinitiator and 13	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/21 22:53
L15	10	L7 and (polyamic acid or polyimide precursor) and photoinitiator and 13 and "522"/\$.ccis.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/21 22:54
L16	1940177	polyimide resin composition and (polyimide precursor or polyamic acid) and photosensitizer	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/21 23:03
L17	1042	16 and cyclohexane near3 diamine	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/21 23:04
L18	205	17 and diaminocyclohexane	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/21 23:09
L19	55	17 and diaminodicyclohexylmethane	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/21 23:07
L20	13543	18 and methylenebis cyclohexylamine	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/21 23:06
L21	5520	20 and salt same solution	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/21 23:06
L22	2	21 and 19	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/21 23:07
L23	61	17 and diaminocyclohexane and "528"/\$.ccis.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/02/21 23:10

WEST Search History

DATE: Monday, February 21, 2005

<u>Hide?</u>	<u>Set Name</u>	<u>Query</u>	<u>Hit Count</u>
<i>DB=USPT,USOC,EPAB,JPAB,DWPI; PLUR=YES; OP=ADJ</i>			
<input type="checkbox"/>	L12	L3 and cyclohexylamine	4
<input type="checkbox"/>	L11	L3 and ?cyclohexylamine	0
<input type="checkbox"/>	L10	L3 and methylenebis cyclohexylamine	0
<input type="checkbox"/>	L9	L8 and methylenebis cyclohexylamine	0
<input type="checkbox"/>	L8	L3 and cyclohexane	15
<input type="checkbox"/>	L7	L3 and ?cyclohexane	0
<input type="checkbox"/>	L6	L3 and dicyclohexane	0
<input type="checkbox"/>	L5	L3 and methylene biscyclohexane	0
<input type="checkbox"/>	L4	L3 and methylenebiscyclohexane	0
<input type="checkbox"/>	L3	resin composition and (polyimide precursor or polyamic acid) and photosensiti?er	257
<input type="checkbox"/>	L2	resin compositin and (polyimide precursor or polyamic acid) and photosensiti?er	0
<input type="checkbox"/>	L1	resin compositin and imidized polyimide precursor and photosensiti?er	0

END OF SEARCH HISTORY

Hit List

Clear	Generate Collection	Print	Fwd Refs	Bkwd Refs
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Search Results - Record(s) 1 through 4 of 4 returned.

1. Document ID: US 6723484 B1

Using default format because multiple data bases are involved.

L12: Entry 1 of 4

File: USPT

Apr 20, 2004

US-PAT-NO: 6723484

DOCUMENT-IDENTIFIER: US 6723484 B1

TITLE: Positive-working photosensitive resin precursor composition

DATE-ISSUED: April 20, 2004

INVENTOR-INFORMATION:

NAME	CITY	STATE	ZIP CODE	COUNTRY
Tomikawa; Masao	Shiga			JP
Okamoto; Naoyo	Aichi			JP
Yoshida; Satoshi	Shiga			JP
Okuda; Ryoji	Shiga			JP

US-CL-CURRENT: 430/192; 430/191, 430/193, 430/270.1

Full	Title	Citation	Front	Review	Classification	Date	Reference	Abstract	Detailed Abstract	Claims	KOMC	Drawn D
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2. Document ID: US 6316170 B1

L12: Entry 2 of 4

File: USPT

Nov 13, 2001

US-PAT-NO: 6316170

DOCUMENT-IDENTIFIER: US 6316170 B1

**** See image for Certificate of Correction ****

TITLE: Developing solution and method of forming polyimide pattern by using the developing solution

DATE-ISSUED: November 13, 2001

INVENTOR-INFORMATION:

NAME	CITY	STATE	ZIP CODE	COUNTRY
Kawamonzen; Yoshiaki	Machida			JP
Matake; Shigeru	Yokohama			JP
Hayase; Rumiko	Yokohama			JP
Mikoshiba; Satoshi	Yamato			JP

US-CL-CURRENT: 430/330; 430/281.1, 430/331

Full	Title	Citation	Front	Review	Classification	Date	Reference	Abstract	Claims	KMPC	Drawn D.
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 3. Document ID: US 6080833 A

L12: Entry 3 of 4

File: USPT

Jun 27, 2000

US-PAT-NO: 6080833

DOCUMENT-IDENTIFIER: US 6080833 A

TITLE: Low-birefringent organic optical component and a spirobiindan polymer

DATE-ISSUED: June 27, 2000

INVENTOR-INFORMATION:

NAME	CITY	STATE	ZIP CODE	COUNTRY
Otsuji; Atsuo	Kanagawa			JP
Takuma; Keisuke	Kanagawa			JP
Suzuki; Rihoko	Kanagawa			JP
Urakami; Tatsuhiro	Kanagawa			JP
Motoshima; Toshihiro	Kanagawa			JP
Yamashita; Wataru	Fukuoka			JP
Yoshimura; Tomomi	Kanagawa			JP
Shibuya; Atsushi	Kanagawa			JP
Sakata; Yoshihiro	Kanagawa			JP
Oikawa; Hideaki	Kanagawa			JP
Ohta; Masahiro	Kanagawa			JP
Ajioka; Masanobu	Kanagawa			JP
Takagi; Masatoshi	Kanagawa			JP
Karasawa; Akio	Kanagawa			JP

US-CL-CURRENT: 528/201; 528/196, 528/198, 528/298

Full	Title	Citation	Front	Review	Classification	Date	Reference	Abstract	Claims	KMPC	Drawn D.
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 4. Document ID: CN 1503927 A, WO 200288845 A1, JP 2002323766 A, US 20040127595 A1

L12: Entry 4 of 4

File: DWPI

Jun 9, 2004

DERWENT-ACC-NO: 2003-058855

DERWENT-WEEK: 200460

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TITLE: Resin composition containing imidized polyimide precursor and photosensitizer, used in patterning resin films on metal wiring of wiring boards

INVENTOR: AKAMATSU, T; HASEGAWA, M ; ISHII, J ; NOMURA, M

PRIORITY-DATA: 2001JP-0125585 (April 24, 2001)

PATENT-FAMILY:

PUB-NO	PUB-DATE	LANGUAGE	PAGES	MAIN-IPC
<u>CN 1503927 A</u>	June 9, 2004		000	G03F007/037
<u>WO 200288845 A1</u>	November 7, 2002	J	061	G03F007/037
<u>JP 2002323766 A</u>	November 8, 2002		024	G03F007/037
<u>US 20040127595 A1</u>	July 1, 2004		000	C08J003/28

INT-CL (IPC): C08 G 73/10; C08 J 3/28; C08 K 5/00; C08 L 79/08; C09 D 5/00; C09 D 179/08; G03 F 7/022; G03 F 7/037; H01 L 21/027

[Full](#) | [Title](#) | [Citation](#) | [Front](#) | [Review](#) | [Classification](#) | [Date](#) | [Reference](#) | [Search](#) | [Print](#) | [Claims](#) | [KMC](#) | [Drawn D](#)

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Term	Documents
CYCLOHEXYLAMINE	15530
CYCLOHEXYLAMINES	477
(3 AND CYCLOHEXYLAMINE).USPT,USOC,EPAB,JPAB,DWPI.	4
(L3 AND CYCLOHEXYLAMINE).USPT,USOC,EPAB,JPAB,DWPI.	4

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[First Hit](#) [Previous Doc](#) [Next Doc](#) [Go to Doc#](#)

End of Result Set

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L12: Entry 4 of 4

File: DWPI

Jun 9, 2004

DERWENT-ACC-NO: 2003-058855

DERWENT-WEEK: 200460

COPYRIGHT 2005 DERWENT INFORMATION LTD

TITLE: Resin composition containing imidized polyimide precursor and photosensitizer, used in patterning resin films on metal wiring of wiring boards

INVENTOR: AKAMATSU, T; HASEGAWA, M ; ISHII, J ; NOMURA, M

PATENT-ASSIGNEE: SONY CHEM CORP (SONY), AKAMATSU T (AKAMI), HASEGAWA M (HASEI), ISHII J (ISHII), NOMURA M (NOMUI)

PRIORITY-DATA: 2001JP-0125585 (April 24, 2001)

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[Search ALL](#)

[Clear](#)

PATENT-FAMILY:

PUB-NO	PUB-DATE	LANGUAGE	PAGES	MAIN-IPC
<input type="checkbox"/> CN 1503927 A	June 9, 2004		000	G03F007/037
<input type="checkbox"/> WO 200288845 A1	November 7, 2002	J	061	G03F007/037
<input type="checkbox"/> JP 2002323766 A	November 8, 2002		024	G03F007/037
<input type="checkbox"/> US 20040127595 A1	July 1, 2004		000	C08J003/28

DESIGNATED-STATES: CN US

APPLICATION-DATA:

PUB-NO	APPL-DATE	APPL-NO	DESCRIPTOR
CN 1503927A	April 17, 2002	2002CN-0808732	
WO 200288845A1	April 17, 2002	2002WO-JP03807	
JP2002323766A	April 24, 2001	2001JP-0125585	
US20040127595A1	April 24, 2001	2002WO-JP03807	Cont of
US20040127595A1	October 24, 2003	2003US-0693842	

INT-CL (IPC): C08 G 73/10; C08 J 3/28; C08 K 5/00; C08 L 79/08; C09 D 5/00; C09 D 179/08; G03 F 7/022; G03 E 7/037; H01 L 21/027

ABSTRACTED-PUB-NO: WO 200288845A

BASIC-ABSTRACT:

NOVELTY - Resin composition has an imidized polyimide precursor and a photosensitizer, and imidization degree of the polyimide precursor is 7.5-36%.

DETAILED DESCRIPTION - The polyimide precursor has polymer structure units of formula (I).

A1 = an aromatic compound structure;

A2 = an alicyclic compound structure.

INDEPENDENT CLAIMS are also included for:

(1) a resin film formation method comprises a coating process which forms a resin film by coating the composition on a target, an exposure method for forming a latent image by exposing the resin film, a developing process for developing the resin film, and an imidization process for imidizing the polyimide precursor by heating the resin film; and

(2) a resin composition manufacture method by forming a salt by reacting 1,4-diaminocyclohexane or 4,4'-methylene-bis cyclohexylamine and an aromatic acid dianhydride in a solvent, reacting the resin solution containing the salt at 80-150 deg. C, reacting the resin solution at 160-250 deg. C to a set imidization degree, and adding a photosensitizer.

USE - Used in patterning resin films on metal wiring of wiring boards.

ADVANTAGE - A film is obtained having excellent light-transmitting properties over a wide wavelength range. The resin composition has a low solubility in a developing solution and the unexposed areas do not dissolve in the developing solution.

ABSTRACTED-PUB-NO: WO 200288845A

EQUIVALENT-ABSTRACTS:

CHOSEN-DRAWING: Dwg.0/16

DERWENT-CLASS: A26 A89 G06 L03 P84 U11 V04

CPI-CODES: A05-J01B; A12-L02B2; G06-D06; L04-C05;

EPI-CODES: U11-A06A; V04-R01A1;

[Previous Doc](#) [Next Doc](#) [Go to Doc#](#)

Hit List

Clear	Generate Collection	Print	Fwd Refs	Bkwd Refs
Generate OACS				

Search Results - Record(s) 1 through 10 of 15 returned.

1. Document ID: US 6791649 B1

Using default format because multiple data bases are involved.

L8: Entry 1 of 15

File: USPT

Sep 14, 2004

US-PAT-NO: 6791649

DOCUMENT-IDENTIFIER: US 6791649 B1

TITLE: Anti-reflection film, polarizing plate comprising the same, and image display device using the anti-reflection film or the polarizing plate

DATE-ISSUED: September 14, 2004

INVENTOR-INFORMATION:

NAME	CITY	STATE	ZIP CODE	COUNTRY
Nakamura; Kenichi	Minami-ashigara			JP
Amimori; Ichiro	Minami-ashigara			JP
Ikeyama; Akihiro	Minami-ashigara			JP
Watanabe; Jun	Minami-ashigara			JP

US-CL-CURRENT: 349/137

Full	Title	Citation	Front	Review	Classification	Date	Reference	Claims	RQIC	Drawn
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2. Document ID: US 6743851 B2

L8: Entry 2 of 15

File: USPT

Jun 1, 2004

US-PAT-NO: 6743851

DOCUMENT-IDENTIFIER: US 6743851 B2

TITLE: Polyimide film

DATE-ISSUED: June 1, 2004

INVENTOR-INFORMATION:

NAME	CITY	STATE	ZIP CODE	COUNTRY
Tanaka; Akira	Kanagawa			JP
Tazaki; Satoshi	Kanagawa			JP
Yoneda; Yasuhiro	Kanagawa			JP
Yokouchi; Kishio	Kanagawa			JP

US-CL-CURRENT: 524/548; 430/270.1, 430/283.1, 524/600, 524/607, 528/126, 528/170,
528/172

[Full](#) | [Title](#) | [Citation](#) | [Front](#) | [Review](#) | [Classification](#) | [Date](#) | [Reference](#) | [Search](#) | [Advanced Search](#) | [Claims](#) | [KOMC](#) | [Drawn D](#)

3. Document ID: US 6734248 B2

L8: Entry 3 of 15

File: USPT

May 11, 2004

US-PAT-NO: 6734248

DOCUMENT-IDENTIFIER: US 6734248 B2

** See image for Certificate of Correction **

TITLE: Pattern forming process using polyimide resin composition

DATE-ISSUED: May 11, 2004

INVENTOR-INFORMATION:

NAME	CITY	STATE	ZIP CODE	COUNTRY
Tanaka; Akira	Kanagawa			JP
Tazaki; Satoshi	Kanagawa			JP
Yoneda; Yasuhiro	Kanagawa			JP
Yokouchi; Kishio	Kanagawa			JP

US-CL-CURRENT: 524/548; 430/270.1, 430/283.1, 430/287.1, 522/164, 524/600, 524/607,
528/126, 528/170, 528/172

[Full](#) | [Title](#) | [Citation](#) | [Front](#) | [Review](#) | [Classification](#) | [Date](#) | [Reference](#) | [Search](#) | [Advanced Search](#) | [Claims](#) | [KOMC](#) | [Drawn D](#)

4. Document ID: US 6600006 B2

L8: Entry 4 of 15

File: USPT

Jul 29, 2003

US-PAT-NO: 6600006

DOCUMENT-IDENTIFIER: US 6600006 B2

TITLE: Positive-type photosensitive polyimide precursor and composition comprising
the same

DATE-ISSUED: July 29, 2003

INVENTOR-INFORMATION:

NAME	CITY	STATE	ZIP CODE	COUNTRY
Jung; Myung Sup	Daejun-Shi			KR
Jung; Sung Kyung	Daejun-Shi			KR
Park; Yong Young	Daejun-Shi			KR
Moon; Bong Seok	Daejun-Shi			KR
Kim; Bong Kyu	Seoul			KR

US-CL-CURRENT: 528/353; 257/E23.119, 257/E23.132, 430/270.1, 525/436, 528/125,

528/126, 528/128, 528/170, 528/171, 528/172, 528/173, 528/174, 528/176, 528/183,
528/185, 528/220, 528/229, 528/26, 528/272

[Full](#) | [Title](#) | [Citation](#) | [Front](#) | [Review](#) | [Classification](#) | [Date](#) | [Reference](#) | [Abstract](#) | [Claims](#) | [KMC](#) | [Drawn](#)

5. Document ID: US 6596445 B1

L8: Entry 5 of 15

File: USPT

Jul 22, 2003

US-PAT-NO: 6596445

DOCUMENT-IDENTIFIER: US 6596445 B1

TITLE: O-acyloxime photoinitiators

DATE-ISSUED: July 22, 2003

INVENTOR-INFORMATION:

NAME	CITY	STATE	ZIP CODE	COUNTRY
Matsumoto; Akira	Kyoto			JP
Oka; Hidetaka	Hyogo			JP
Ohwa; Masaki	Kobe			JP
Kura; Hisatoshi	Hyogo			JP
Birbaum; Jean-Luc	Binningen			CH
Dietliker; Kurt	Allschwil			CH

US-CL-CURRENT: 430/7; 430/270.1, 522/39, 564/254

[Full](#) | [Title](#) | [Citation](#) | [Front](#) | [Review](#) | [Classification](#) | [Date](#) | [Reference](#) | [Abstract](#) | [Claims](#) | [KMC](#) | [Drawn](#)

6. Document ID: US 6316170 B1

L8: Entry 6 of 15

File: USPT

Nov 13, 2001

US-PAT-NO: 6316170

DOCUMENT-IDENTIFIER: US 6316170 B1

** See image for Certificate of Correction **

TITLE: Developing solution and method of forming polyimide pattern by using the developing solution

DATE-ISSUED: November 13, 2001

INVENTOR-INFORMATION:

NAME	CITY	STATE	ZIP CODE	COUNTRY
Kawamorzen; Yoshiaki	Machida			JP
Matake; Shigeru	Yokohama			JP
Hayase; Rumiko	Yokohama			JP
Mikoshiba; Satoshi	Yamato			JP

US-CL-CURRENT: 430/330; 430/281.1, 430/331

[Full](#) | [Title](#) | [Citation](#) | [Front](#) | [Review](#) | [Classification](#) | [Date](#) | [Reference](#) | [Claims](#) | [KIMC](#) | [Drawn D](#)

7. Document ID: US 6310135 B1

L8: Entry 7 of 15

File: USPT

Oct 30, 2001

US-PAT-NO: 6310135

DOCUMENT-IDENTIFIER: US 6310135 B1

** See image for Certificate of Correction **

·TITLE: Polyimide resin composition

DATE-ISSUED: October 30, 2001

INVENTOR-INFORMATION:

NAME	CITY	STATE	ZIP CODE	COUNTRY
Tanaka; Akira	Kanagawa			JP
Tazaki; Satoshi	Kanagawa			JP
Yoneda; Yasuhiro	Kanagawa			JP
Yokouchi; Kishio	Kanagawa			JP

US-CL-CURRENT: 524/548; 430/270.1, 430/283.1, 524/600, 524/607, 528/126, 528/170,
528/172, 528/188, 528/350, 528/353

[Full](#) | [Title](#) | [Citation](#) | [Front](#) | [Review](#) | [Classification](#) | [Date](#) | [Reference](#) | [Claims](#) | [KIMC](#) | [Drawn D](#)

8. Document ID: US 6080833 A

L8: Entry 8 of 15

File: USPT

Jun 27, 2000

US-PAT-NO: 6080833

DOCUMENT-IDENTIFIER: US 6080833 A

TITLE: Low-birefringent organic optical component and a spirobiindan polymer

DATE-ISSUED: June 27, 2000

INVENTOR-INFORMATION:

NAME	CITY	STATE	ZIP CODE	COUNTRY
Otsuji; Atsuo	Kanagawa			JP
Takuma; Keisuke	Kanagawa			JP
Suzuki; Rihoko	Kanagawa			JP
Urakami; Tatsuhiro	Kanagawa			JP
Motoshima; Toshihiro	Kanagawa			JP
Yamashita; Wataru	Fukuoka			JP
Yoshimura; Tomomi	Kanagawa			JP
Shibuya; Atsushi	Kanagawa			JP
Sakata; Yoshihiro	Kanagawa			JP

Oikawa; Hideaki	Kanagawa	JP
Ohta; Masahiro	Kanagawa	JP
Ajioka; Masanobu	Kanagawa	JP
Takagi; Masatoshi	Kanagawa	JP
Karasawa; Akio	Kanagawa	JP

US-CL-CURRENT: 528/201; 528/196, 528/198, 528/298

[Full](#) | [Title](#) | [Citation](#) | [Front](#) | [Review](#) | [Classification](#) | [Date](#) | [Reference](#) | [Search](#) | [Claims](#) | [KOMC](#) | [Drawn](#)

9. Document ID: US 5530036 A

L8: Entry 9 of 15

File: USPT

Jun 25, 1996

US-PAT-NO: 5530036

DOCUMENT-IDENTIFIER: US 5530036 A

TITLE: Epoxy group-containing copolymer and radiation sensitive resin compositions thereof

DATE-ISSUED: June 25, 1996

INVENTOR-INFORMATION:

NAME	CITY	STATE	ZIP CODE	COUNTRY
Sano; Kimiyasu	Yokohama			JP
Endo; Masayuki	Yokohama			JP
Shimada; Atsufumi	Yokohama			JP
Yokoyama; Yasuaki	Yokkaichi			JP
Bessho; Nobuo	Yokohama			JP

US-CL-CURRENT: 522/79; 522/114, 522/116, 522/120, 522/121, 522/122

[Full](#) | [Title](#) | [Citation](#) | [Front](#) | [Review](#) | [Classification](#) | [Date](#) | [Reference](#) | [Search](#) | [Claims](#) | [KOMC](#) | [Drawn](#)

10. Document ID: US 5518864 A

L8: Entry 10 of 15

File: USPT

May 21, 1996

US-PAT-NO: 5518864

DOCUMENT-IDENTIFIER: US 5518864 A

TITLE: Method of forming polyimide film pattern

DATE-ISSUED: May 21, 1996

INVENTOR-INFORMATION:

NAME	CITY	STATE	ZIP CODE	COUNTRY
Oba; Masayuki	Yokohama			JP
Hayase; Rumiko	Kawasaki			JP

Kihara; Naoko	Matsudo	JP
Hayase; Shuzi	Kawasaki	JP
Mikogami; Yukihiro	Yokohama	JP
Nakano; Yoshihiko	Tokyo	JP
Oyasato; Naohiko	Kawaguchi	JP
Matake; Shigeru	Yokohama	JP
Takano; Kei	Yokohama	JP

US-CL-CURRENT: [430/325](#); [430/165](#), [430/167](#), [430/189](#), [430/192](#), [430/193](#), [430/197](#),
[430/326](#), [430/330](#)

[Full](#) | [Title](#) | [Citation](#) | [Front](#) | [Review](#) | [Classification](#) | [Date](#) | [Reference](#) | [Search](#) | [Print](#) | [Claims](#) | [EPOC](#) | [Drawn D](#)

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Term	Documents
CYCLOHEXANE	125783
CYCLOHEXANES	2301
(3 AND CYCLOHEXANE).USPT,USOC,EPAB,JPAB,DWPI.	15
(L3 AND CYCLOHEXANE).USPT,USOC,EPAB,JPAB,DWPI.	15

Display Format: [-] [Change Format](#)

[Previous Page](#) [Next Page](#) [Go to Doc#](#)

Hit List

Clear	Generate Collection	Print	Fwd Refs	Bkwd Refs
Generate OACS				

Search Results - Record(s) 11 through 15 of 15 returned.

11. Document ID: US 5399604 A

Using default format because multiple data bases are involved.

L8: Entry 11 of 15

File: USPT

Mar 21, 1995

US-PAT-NO: 5399604

DOCUMENT-IDENTIFIER: US 5399604 A

TITLE: Epoxy group-containing resin compositions

DATE-ISSUED: March 21, 1995

INVENTOR-INFORMATION:

NAME	CITY	STATE	ZIP CODE	COUNTRY
Sano; Kimiyasu	Yokohama			JP
Endo; Masayuki	Yokohama			JP
Shimada; Atsufumi	Yokohama			JP
Yokoyama; Yasuaki	Yokkaichi			JP
Bessho; Nobuo	Yokohama			JP

US-CL-CURRENT: 524/356; 522/114, 522/120, 522/129, 524/366, 524/378, 524/379,
524/755, 524/761, 524/765, 524/769, 524/770, 525/100, 526/329.1, 526/329.2,
526/329.6, 528/27

[Full](#) | [Title](#) | [Citation](#) | [Front](#) | [Review](#) | [Classification](#) | [Date](#) | [Reference](#) | [Assignee](#) | [Inventor](#) | [Claims](#) | [KOMC](#) | [Drawn](#)

12. Document ID: US 5385808 A

L8: Entry 12 of 15

File: USPT

Jan 31, 1995

US-PAT-NO: 5385808

DOCUMENT-IDENTIFIER: US 5385808 A

TITLE: Photosensitive resin composition and semiconductor apparatus using it

DATE-ISSUED: January 31, 1995

INVENTOR-INFORMATION:

NAME	CITY	STATE	ZIP CODE	COUNTRY
Tokoh; Akira	Tokyo			JP
Sashida; Nobuyuki	Nobuyuki			JP
Takeuchi; Etsu	Yokohama			JP

Hirano; Takashi

Yokohama

JP

US-CL-CURRENT: 430/283.1; 430/281.1

Full	Title	Citation	Front	Review	Classification	Date	Reference				Claims	KOMC	Drawn D
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13. Document ID: US 5348835 A

L8: Entry 13 of 15

File: USPT

Sep 20, 1994

US-PAT-NO: 5348835

DOCUMENT-IDENTIFIER: US 5348835 A

TITLE: Photosensitive resin composition for forming polyimide film pattern comprising an o-quinone diazide photosensitive agent

DATE-ISSUED: September 20, 1994

INVENTOR-INFORMATION:

NAME	CITY	STATE	ZIP CODE	COUNTRY
Oba; Masayuki	Yokohama			JP
Hayase; Rumiko	Kawasaki			JP
Kihara; Naoko	Matsudo			JP
Hayase; Shuzi	Kawasaki			JP
Mikogami; Yukihiro	Yokohama			JP
Nakano; Yoshihiko	Tokyo			JP
Oyasato; Naohiko	Kawaguchi			JP
Matake; Shigeru	Yokohama			JP
Takano; Kei	Yokohama			JP

US-CL-CURRENT: 430/192; 430/165, 430/167, 430/189, 430/191, 430/193, 430/197,
430/330, 525/436, 528/353

Full	Title	Citation	Front	Review	Classification	Date	Reference				Claims	KOMC	Drawn D
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14. Document ID: US 5238784 A

L8: Entry 14 of 15

File: USPT

Aug 24, 1993

US-PAT-NO: 5238784

DOCUMENT-IDENTIFIER: US 5238784 A

TITLE: Photosensitive resin composition with polyamic acid polymer

DATE-ISSUED: August 24, 1993

INVENTOR-INFORMATION:

NAME	CITY	STATE	ZIP CODE	COUNTRY
Tokoh; Akira	Tokyo			JP

Sashida; Nobuyuki	Yokohama	JP
Takeuchi; Etsu	Yokohama	JP
Hirano; Takashi	Yokohama	JP

US-CL-CURRENT: 430/283.1; 430/191, 430/192, 430/196, 430/197, 522/136, 522/137,
522/139, 522/140, 522/906

[Full](#) | [Title](#) | [Citation](#) | [Front](#) | [Review](#) | [Classification](#) | [Date](#) | [Reference](#) | [Search](#) | [Print](#) | [Fwd Refs](#) | [Bkwd Refs](#) | [Claims](#) | [KWMC](#) | [Drawn D](#)

15. Document ID: US 4650849 A

L8: Entry 15 of 15

File: USPT

Mar 17, 1987

US-PAT-NO: 4650849

DOCUMENT-IDENTIFIER: US 4650849 A

TITLE: Photosensitive curable resin composition

DATE-ISSUED: March 17, 1987

INVENTOR-INFORMATION:

NAME	CITY	STATE	ZIP CODE	COUNTRY
Nishimura; Yoshiaki	Tokyo			JP
Okinoshima; Hiroshige	Gunma			JP
Yamada; Seiya	Gunma			JP
Kashiwagi; Tsutomu	Gunma			JP

US-CL-CURRENT: 528/26; 528/31

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Term	Documents
CYCLOHEXANE	125783
CYCLOHEXANES	2301
(3 AND CYCLOHEXANE).USPT,USOC,EPAB,JPAB,DWPI.	15
(L3 AND CYCLOHEXANE).USPT,USOC,EPAB,JPAB,DWPI.	15

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